

A-3-3 A 64K Dynamic MOS-RAM Using Short-Channel, Channel-Dope Technology

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A 64K dynamic MOS-RAM organized as 16 kwords X 4 bits has been realized by short-channel, channel-dope technology. Also, the improved low power sense amplifiers and a multiplexed address system have been developed. The access time and power dissipation are 110 ns and 150 mW, respectively, at the cycle time of 400 ns.

The innovative single-level Si-gate MOS technologies employed for the present 64K dynamic RAM are summarized as follows : 1. Lightly doped Si substrate, $\approx 10^{15} \text{ cm}^{-3}$; 2. Thin SiO_2 gate film thickness, 400 Å ; 3. Phosphorus diffused shallow junction depth, 0.5 μm ; 4. Short effective channel length having channel dope region, 2 μm ; 5. Low poly-Si sheet resistivity, 13 ohm/ $\square$. Typical gate threshold voltage of an MOS transistor is 0.85 V for 1 V drain voltage. The effect of channel dope will be summarized latter.

A photomicrograph of the 64K RAM and its mask layout are shown in Figs. 1A and 1B, respectively. The chip area is 4.72 mm X 7.05 mm which is assembled in a standard 22 pin DIP package. The memory cell size is 15 μm X 18 μm in which poly-Si word and aluminum bit lines cross each other. The RAM chip has four pads for data-in and four others for data-out, and fourteen addresses are multiplexed on seven address input pads. Each 16K bit block is composed of two balanced 64 X 128 bit arrays sharing 128 sense amplifiers. Key aspects of the 64K dynamic RAM is summarized in Table I, in which typical DC supply voltages are 7 V for V_{DD} and -2 V for V_{BB} . The memory cell yields a bit line capacitance ratio C_B/C_S of about 7 in the present design.

Figs. 2A and 2B show the sense amplifier circuit and its simulated signal waveforms. This circuit is a variation of the simple cross coupled latch, which gives perfect dynamic operation. Two balancing transistors connect parallel with the cross coupled transistors, one another, and achieve early potential balance between a complementary bit line pair in reset mode. Although 80 mV is estimated as the worst case differential signal input, the memory cell gives a sense node difference of 170 mV to the bit line pair. No static current flow is observed in the sense amplifier circuit. During a typical read cycle, $t_{\text{cycle}}=400\text{ns}$, the 512 sense amplifiers dissipate approximately 60 mW which is less than 40 percent of the chip power.

Fig.3 shows waveforms of the 64K dynamic RAM, where t_{access} and t_{cycle} are 110 ns and 300 ns, respectively. The operating conditions are $T=25^\circ\text{C}$, $V_{DD}=7\text{ V}$, $V_{BB}=-2\text{ V}$ in the marching test mode. The present channel-doped RAM (SAMPLE A) shmoo-plot shows wide supply-voltage-margin as shown in Fig.4 in comparison with that of SAMPLE B fabricated on highly impurity-concentrated substrate without channel doping. Other device features are shown in Table II. In conclusion, the present 64K RAM fabricated using channel-dope, short-channel technology has realized the wide operating range and high speed operation.

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Fig.1A 64K RAM Chip Microphotograph.

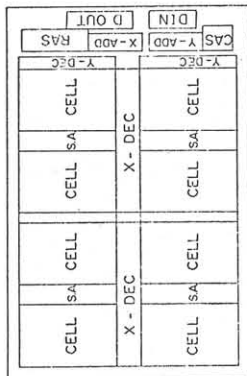


Fig.1B Chip Layout.

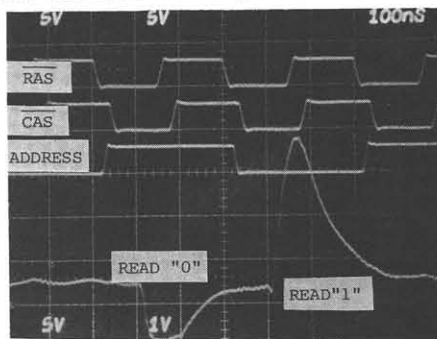


Fig.3 64K RAM Waveforms

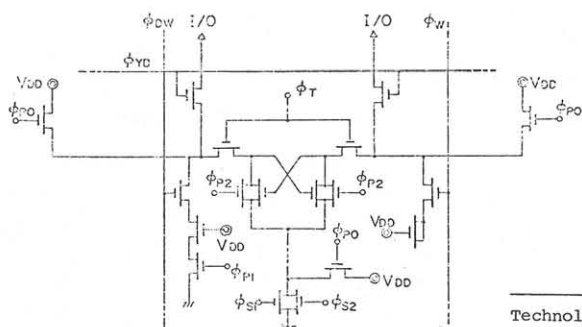


Fig.2A Sense Circuit.

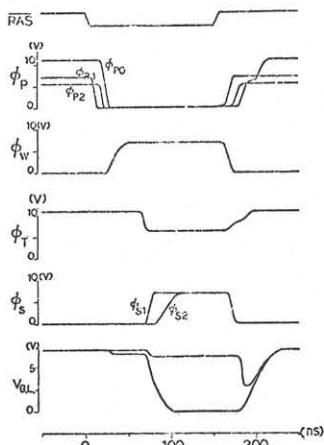


Fig.2B Simulated waveforms.

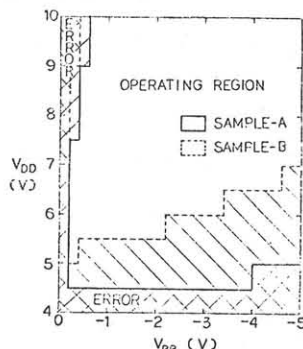


Fig.4 64K RAM Shmoo Plot in the marching test mode.

Technology	Single Poly-Si Nch-MOS
Organization	16 kwords X 4 bits
Memory cell	1 Tr Cell
Cell size	15 μm X 18 μm
Chip size	4.72 mm X 7.05 mm
Supply voltage	7 V, -2 V
I/O levels	TTL (including RAS, CAS)
Address	Multiplexed address
Refresh	128 cycle / 2 ms

Table I. 64K RAM Characteristics

	Sample A	Sample B
Substrate Concentration	$1 \times 10^{15} \text{ cm}^{-3}$	$1.3 \times 10^{16} \text{ cm}^{-3}$
Gate oxide Film	400 $\text{\AA}$	400 $\text{\AA}$
Effective Channel Length	2 μm	2 μm
Threshold Voltage for $V_D=1 \text{ V}$	0.85 V	0.95 V
Access Time	110 ns	150 ns
Cycle Time	300 ns	400 ns
Power Dissipation (at 400 ns cycle time)	<150 mW	<120 mW
Standby Power	<15 mW	<10 mW

Table II. Typical 64K RAM Features